



**PATENT**  
Customer No. 23494  
Attorney Docket No. TI-25250  
Application No.: 09/199,829

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Application of:

SMITH et al.

**Application No.: 09/199,829**

**Filed: November 25, 1998**

For: HYDROGEN PLASMA  
PHOTORESIST STRIP AND  
POLYMERIC RESIDUE CLEANUP  
PROCESS FOR OXYGEN-  
SENSATIVE MATERIALS

**Group Art Unit: 2823**

**Examiner: Julio J. MALDONADO**

# MAIL STOP AMENDMENT

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

**Sir:**

## PETITION FOR EXTENSION OF TIME

Applicant hereby petitions for a one month extension of time to reply to the Office Action of June 14, 2005.

Please grant any extensions of time required to enter this response and charge any additional required fees to the Texas Instruments Deposit Account 20-0668.

Respectfully submitted,

**Dated: October 5, 2005**

**By:**

Jonathan A. Hack  
Reg. No. 47,623

Timothy M. Hsieh  
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